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Omkar K. Suryadevara

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U.S. Patent and Trademark Office; U.S. DEPARTMENT OF COMMERCE Under the Paperwork Reduction Act of 1995, no persons are required to respond to a collection of information unless it displays a valid OMB control number. 10/813,407 **Application Number** RANSMITTAL March 29, 2004 **Filing Date** First Inventor Jiping Li **FORM** MAR 2 5 2005 Confirmation No. 5642 2811 **Group Art Unit** all correspondence after initial filing) **Examiner Name** Unknown Total Number Of Pages In This Submission **BOX016 US** Attorney Docket No. **ENCLOSURES** (check all that apply) Fee Transmittal Form Assignment Papers After Allowance Communication to (for an Application) (1 page in duplicate) Group Fee Attached -- Credit Appeal Communication to Board of Drawing(s) Card Payment Form (1 pg) Appeals and Interferences Appeal Communication to Group Amendment / Reply Licensing-related Papers (Appeal Notice, Brief, Reply Brief) After Final Petition **Proprietary Information** Petition to Convert to a Affidavits/declarations Status Letter **Provisional Application** Power of Attorney, Revocation of Other Enclosure(s) (please identify Previous Powers; And Statement Extension of Time Request below): Under 37 CFR 3.73(b) Terminal Disclaimer RETURN RECEIPT POSTCARD PTO Form 1449 (5 pages) Express Abandonment Request Request for Refund Copies of 50 cited references Information Disclosure Statement (2 CD, Number of CD(s)_ pages) Certified Copy of Priority Document(s) Remarks This is a Response to Missing Parts/ Incomplete Application under 37 CFR Please charge Deposit Account 50-2263 for any underpaid fee. 1.52 or 1.53 Copy of Notice To File Missing Parts (2 pages) SIGNATURE OF APPLICANT, ATTORNEY OR AGENT Firm Omkar K. Suryadevara (Reg. No. 36,320) Silicon Valley Patent Group LLP Individual Name 2350 Mission College Boulevard, Suite 360 Santa Clara, California 95054 Signature Date CERTIFICATE OF MAILING BY "FIRST CLASS" I hereby certify that this paper or fee is being deposited with the United States Postal Service with sufficient postage as first class mail in an envelope addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450 on the below date.

March 23, 2005

Date



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Inventors: Jiping Li; Peter G. Borden; Edgar B. Genio

Assignee: Applied Materials, Inc.

Title: High Throughput Measurement Of Via Defects In Interconnects

Serial No.: 10/813,407 Filing Date: March 29, 2004

Examiner: Unknown Group Art Unit: 2811

Docket No.: BOX016 US Confirmation No: 5642

Santa Clara, California March 23, 2005

MAIL STOP AMENDMENT COMMISSIONER FOR PATENTS P.O. BOX 1450 ALEXANDRIA, VA 22313-1450

INFORMATION DISCLOSURE STATEMENT UNDER 37 CFR §1.97(b)

Dear Sir:

Pursuant to 37 C.F.R. § 1.56, §1.97 and §1.98, the Applicants submit for consideration in the above-identified patent application the documents listed on the accompanying Form PTO-1449. Copies of references numbered <u>47-96</u> are submitted herewith. The Examiner is requested to make these documents of record. The remaining references are not attached hereto, because these references are issued patents or publications which are readily available in the U.S. Patent and Trademark Office.

In addition, Applicants submit for the Examiner's consideration, the prosecution histories of ten co-owned applications/patents, which are identified in the attached PTO-1449 as items 97-106. The Applicants presume that the Examiner has access to and will review the cited applications/patents and the files thereof for any office actions, amendments or other materials that may be relevant to the patentability of the claims of the present application.

Citation of these prosecution histories (including the arguments against patentability advanced by Examiners in their respective Office Actions and the Applicants' arguments in

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2350 Mission College Blvd. Suite 360 Santa Clara, CA 95054 (408) 982-8200 FAX (408) 982-8210 the corresponding Amendments) is in accordance with the recent case DAYCO PRODUCTS, INC. v. TOTAL CONTAINMENT, INC., 02-1497, decided May 23, 2003 by the Court of Appeals for the Federal Circuit. The Examiner is presumed to be knowledgeable about the current case law, including the above-mentioned Dayco case. However, if the Examiner needs a copy of the Dayco case, please call the undersigned.

For any of the following U.S. patent application(s) cited in the attached PTO-1449 that are currently pending, the Applicants further presume that the Examiner will consider any **future** office actions, amendments or other materials in the file thereof that may be relevant to the patentability of the claims herein. If the Applicants' understanding in this regard is not correct, please notify the undersigned so that copies of any such documents can be submitted to the Examiner.

This Information Disclosure Statement is submitted pursuant to 37 CFR §1.97(b) as it is within three months of the filing date of a national application other than a continued prosecution application and/or before the mailing of a first Office Action on the merits. Accordingly, no fee is required.

Applicants would appreciate the Examiner initialing and returning the Form PTO-1449, indicating that the information has been considered and made of record herein.

The information contained in this Information Disclosure Statement is to the best of my knowledge and is not to be construed as a representation that: (i) a complete search has been made; (ii) additional information material to the examination of this application does not exist; (iii) the information, protocols, results and the like reported by third parties are accurate or enabling; or (iv) the above information constitutes prior art to the subject invention.

CERTIFICATE OF MAILING BY "FIRST CLASS"

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Attorney for Applicant(s)

Date of Signature

Respectfully submitted,

Omkar K. Suryadevara Attorney for Applicant(s)

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		Sheet 1 01 3
Department of Commerce, Patent and Trademark Office	Application No.:	10/813,407
	Filing Date:	March 29, 2004
(MAR 2 5 2005 &	First Named Inventor:	Jiping Li
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Use several sheets if necessary)	Group Art Unit:	2811
	Examiner Name:	Unknown
	Confirmation No.:	5642
	Attorney Docket No.:	BOX016 US

			U.S. Pa	tent Documents			
*Examiner Intials		Document Number	Date	Name	Class	Subclass	Filing Date if Appropriate
	1.	6,489,801	12/3/02	Borden et al.	324	766	
	2.	6,812,047	11/2/04	Borden et al.	438	16	-
	3.	5,966,019	10/12/99	Borden	324	752	
	4.	5,377,006	12/27/94	Nakata	356	349	
	5.	6,323,951	11/27/01	Borden et al.	356	502	
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	11.	4,255,971	3/17/81	Rosencwaig	73	606	
	12.	4,579,463	4/1/86	Rosencwaig et al.	374	57	
	13.	4,632,561	12/30/86	Rosencwaig et al.	356	432	
· · · · · · · · · · · · · · · · · · ·	14.	4,636,088	1/13/87	Rosencwaig et al.	374	5	<u> </u>
	15.	4,750,822	6/14/88	Rosencwaig et al.	324	445	
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Examiner:

Date Considered:

^{*} Examiner: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication with applicant.

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U.S. Department of Commerce, Patent and Trademark Office			Application No.:	10/813			
			Filing Date:		29, 2004		
			First Named Inventor		Li		
			Group Art Unit:	2811		-	
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(Us	e several sheets if neces	ssary)	Confirmation No.:	5642			
			Attorney Docket No.	: BOX0	16 US		
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						Tran	slatio
	Document	Date	Country	Class	Subclass	Yes	No
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Examiner:	Date Considered:
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U.S. Department of Commerce, Patent and Trademark Office		Application No.:	10/813,	407			
		Filing Date:	March :	March 29, 2004			
		First Named Inventor: Jiping Li		i			
			Group Art Unit:	2811			
INFORMATI	ON DISC	LOSURE STATEMENT	Γ BY APPLICANT	Examiner Name:	Examiner Name: Unknown Confirmation No.: 5642		
	(Use s	everal sheets if necessary	y)	Confirmation No.:			
				Attorney Docket No.:	BOX01	6 US	
	50.	ISR PCT/ US99/12999	09.06.1999	wo	G01L	21/17	
<u> </u>	51.	ISR PCT/US03/06239	02.28.2003	WO	G01L	21/55	
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	53.	ISR PCT/US03/06379	02.28.2003	wo	G01N	21/88	
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Examiner:				Date Considered:			-

U.S. Department of Commerce, Patent and Trademark Office	Application No.:	10/813,407
, , , , , , , , , , , , , , , , , , , ,	Filing Date:	March 29, 2004
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99.	US Appl. No. 10/090,316 entitled "Apparatus and Method For Measuring A Property Of A Layer In A Multilayered Structure"
100.	US Appl. No. 09/521,232 entitled "Evaluating A Property Of A Multilayered Structure"
101.	US Appl. No. 10/977,380 entitled "Evaluating A Property Of A Multilayered Structure"
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103.	US Appl. No. 10/090,262 entitled "Evaluating A Multilayered Structure For Voids"
104.	US Appl. No. 10/984,463 entitled "Evaluating A Multilayered Structure For Voids"
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